

Nov. 10, 2005

IEUVI Contamination TWG meeting, San Diego

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IEUVI Resist TWG meeting

# ASET update

ASET EUV Process Technology Laboratory  
Iwao Nishiyama

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## Exposure tool

### ■ HiNA-3

- Activity was shifted from Tool evaluation phase to Resist evaluation

### ■ MET of Berkeley

- Start to use Berkeley MET
- Purposes are
  - learning on Exposure tool
  - Use programmable illuminator
  - Calibration on photosensitivity

## Resist Evaluation

- Collaboration with Resist suppliers
- Search CA resists which has 30 nm resolution
- Molecular resist evaluation with NEDO foundation
- LER evaluation
- Outgas evaluation using newly completed apparatus

# Outgas Evaluation Apparatus at SBL-2 of Super ALIS

